

## PATENT

Atty. Dkt. No. AMAT/6199/DISPLAY/AKT/RKK

**IN THE CLAIMS:**

Please cancel claims 1-4 and 13 without prejudice and amend the claims as follows:

1-7. (Cancelled)

8. (Currently Amended) An apparatus for supporting a substrate, comprising:  
a chamber body having at least one substrate access port;  
at least one support member disposed in the chamber body;  
at least one socket disposed in the support member and having a ball support surface and a formed end; and  
a ball rotatably disposed on each the ball support surface and retained in the socket by the formed end, ~~each the~~ ball adapted to contact and support the substrate in a spaced-apart relation to the support member.

9-13. (Canceled)

14. (Original) The apparatus of claim 8, wherein the ball has a surface roughness of 4 micro-inches or smoother.

15. (Previously Presented)) The apparatus of claim 8 further comprising:  
a plurality of mounting pins coupled to the support member, each pin coupled to a respective spacer.

16. (Cancelled)

17. (Currently Amended) The apparatus of claim 8, wherein ~~at least one of the balls~~ at least one support member is positioned to support a center portion of the substrate.

18. (Currently Amended) The apparatus of claim 8, wherein ~~some of a plurality of the support members~~ balls support a perimeter portion of the substrate and at least one of

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the ~~balls~~ at least one support member is positioned to support a center portion of the substrate.

19. (Currently Amended) The apparatus of claim 8, wherein a plurality of spacers having fixed top surfaces support a perimeter portion of the substrate and at least one of the ~~balls~~ at least one support member is positioned to support a center portion of the substrate.

20. (Currently Amended) The apparatus of claim 8, wherein the ~~balls are~~ ball is coated or plated.

21. (Currently Amended) The apparatus of claim 8, wherein the ~~balls are~~ ball is coated or plated chromium, an aluminum alloy, silicon nitride, or tungsten nitride.

22-46. (Cancelled)

47. (Currently Amended) Apparatus for supporting a substrate in a chamber body having at least one substrate support member coupled to the chamber body, comprising:

a spacer body having a first portion and a second portion, the first portion adapted to interface with the support member;

a socket disposed in the second portion and having a ball support surface and a formed end; and

a ball rotatably disposed on the ball support surface in the socket and retained in the socket by the formed end, wherein the ball has a surface roughness of 4 micro-inches or smoother, the ball adapted to contact and support a substrate thereon.

48. (Previously Presented) The apparatus of claim 47, wherein the ball is electropolished.

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49. (Previously Presented) The apparatus of claim 47, wherein the ball is at least one of coated or plated.

50. (Previously Presented) The apparatus of claim 49, wherein the ball is coated or plated with chromium, an aluminum alloy, silicon nitride, or tungsten nitride.

51. (Previously Presented) The apparatus of claim 47, wherein the ball support surface has a radius greater than a radius of the ball.

52. (Previously Presented) The apparatus of claim 8, wherein the balls are electropolished.

53-58. (Cancelled)

59. (Previously Presented) The apparatus of claim 8, further comprising:  
a cassette movably disposed within the chamber, wherein the cassette is coupled to a plurality of support members; and  
a cooling plate disposed within the chamber.